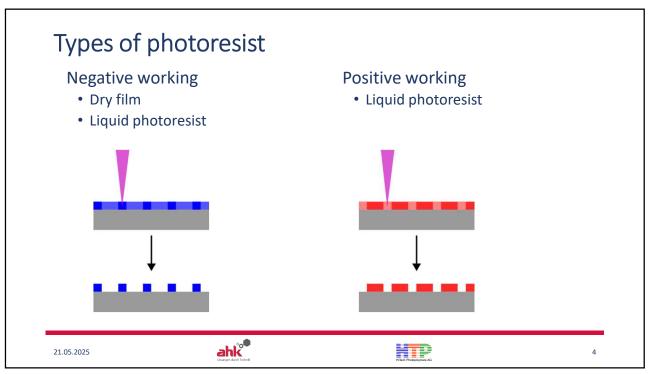
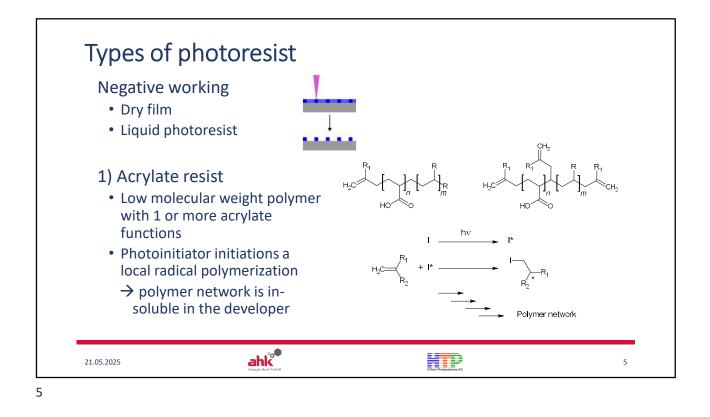
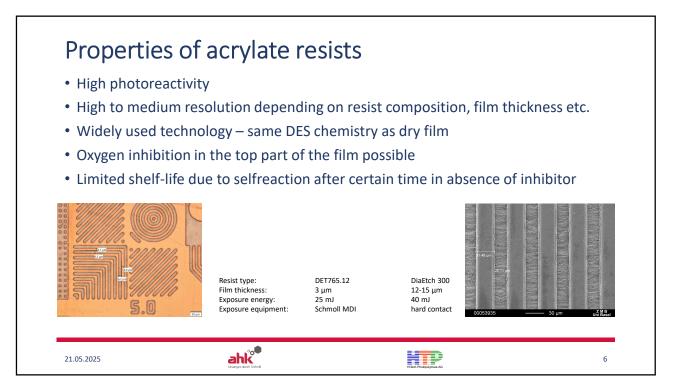
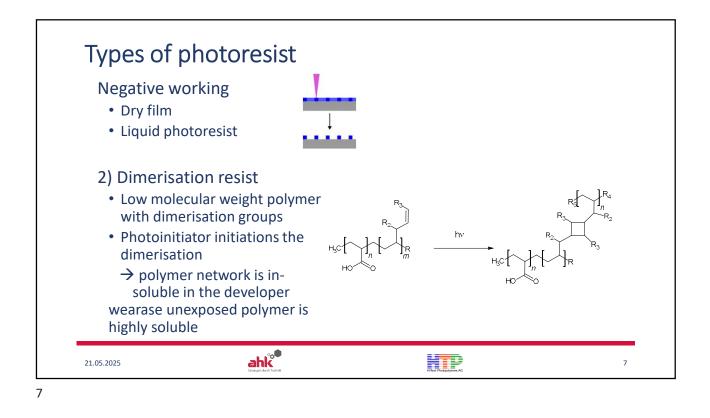


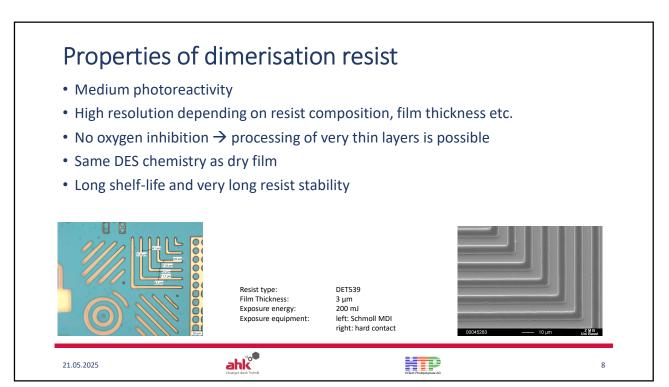
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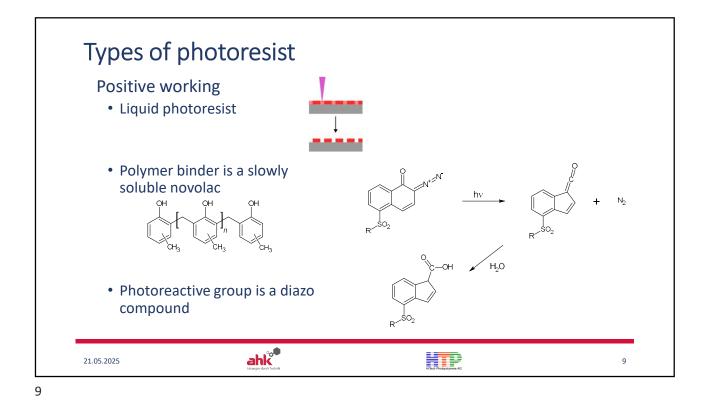


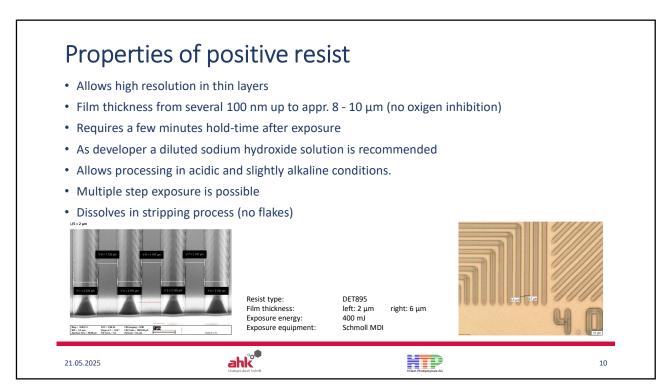


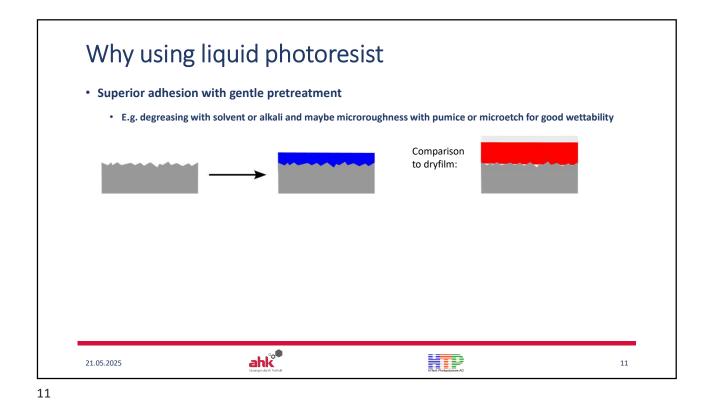


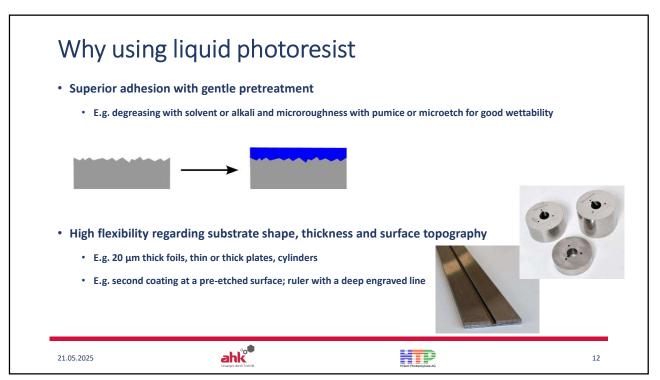


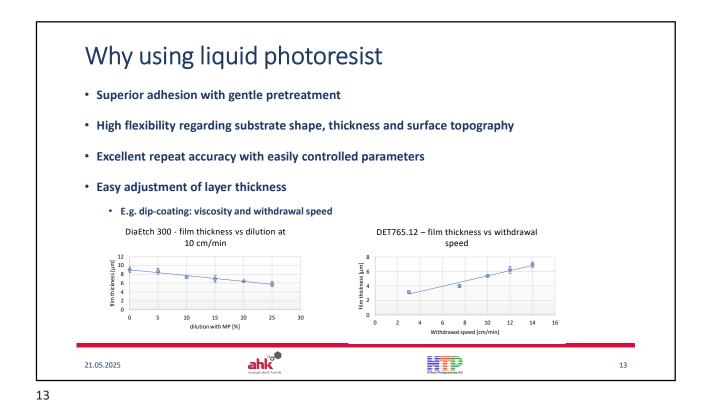


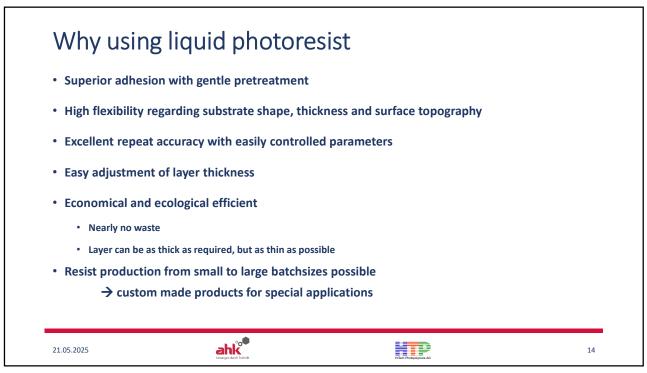


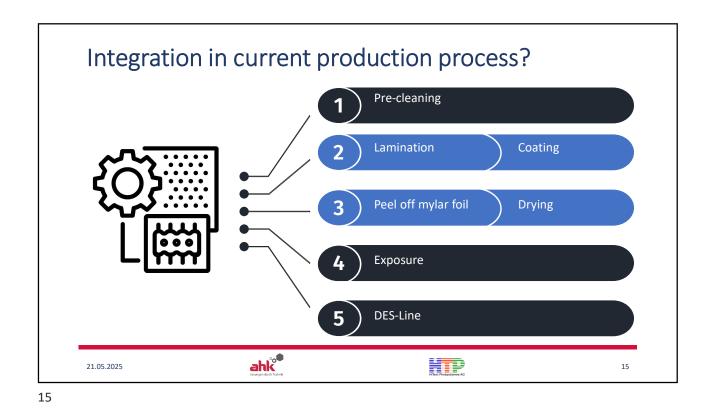


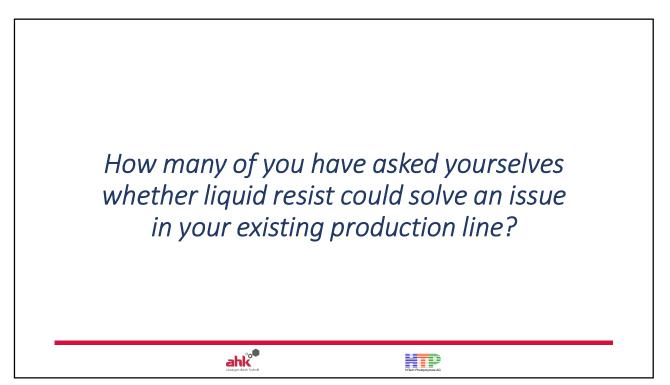


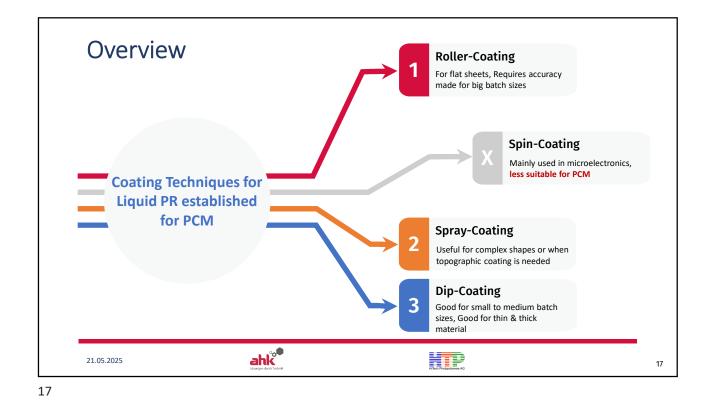


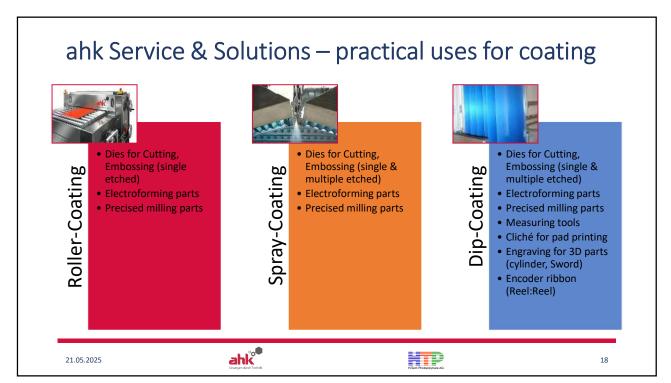


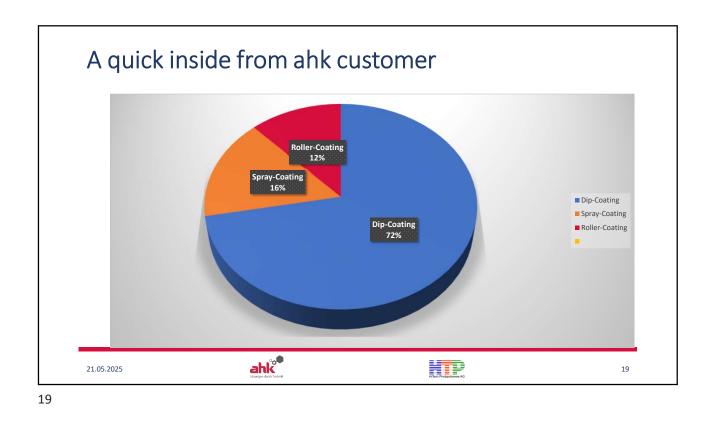


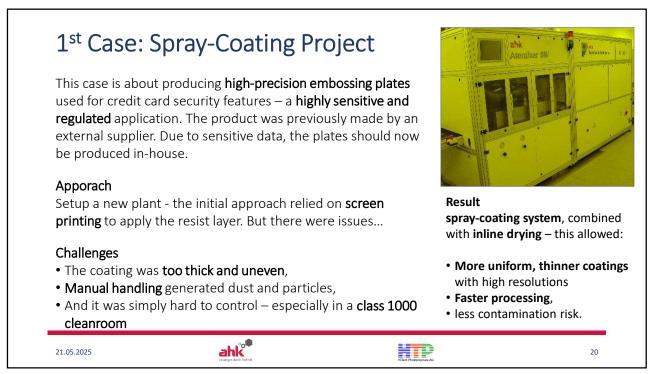


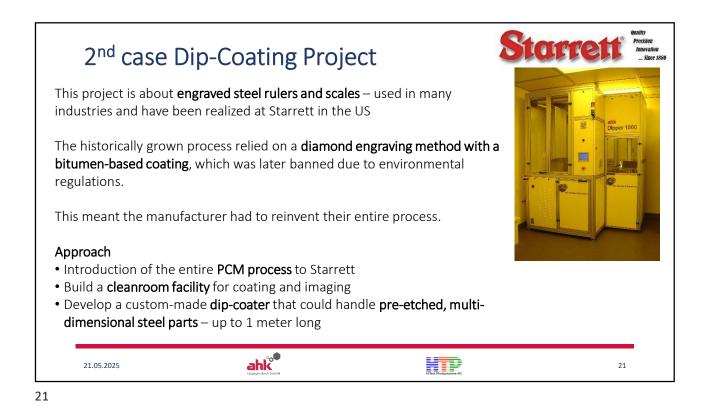


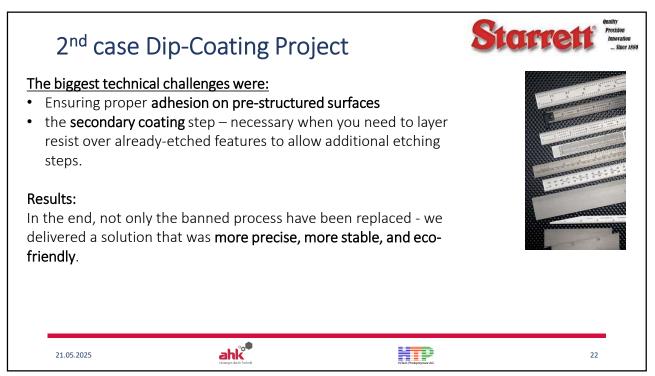


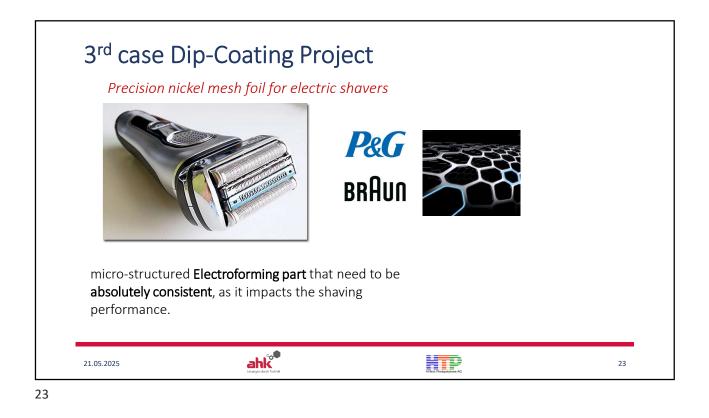


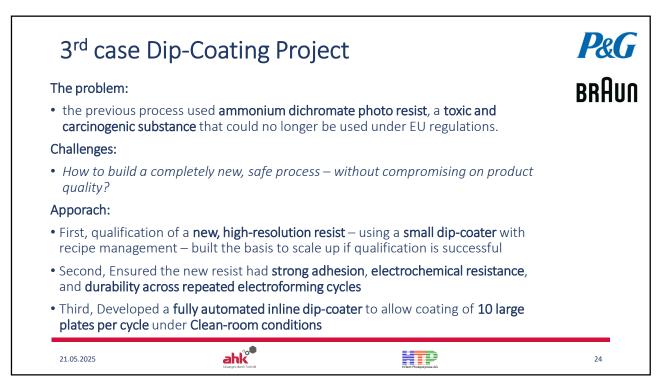




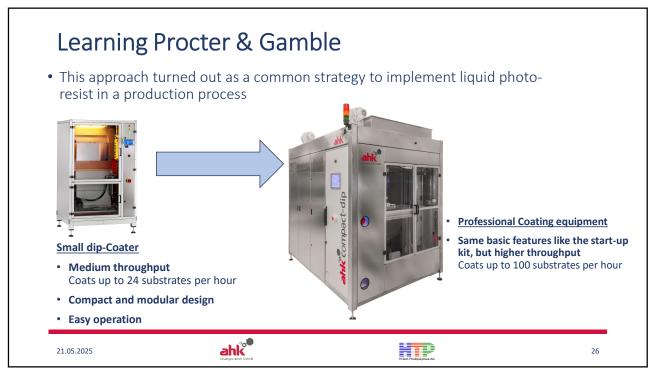








<ul> <li>3rd case Dip</li> <li>Results:</li> <li>Professional in-line processing equipm</li> <li>A healthier, compl</li> <li>A fully scalable wo</li> <li>no loss in perform</li> <li>It's a great example advantages.</li> </ul>	e batch hent iant process irkflow ance	roject	BRAU
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Thank you very	much for your attention!
21.05.2025	